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(54) Title: A HETEROJUNCTION BIPOLAR TRANSISTOR (HBT) WITH PERIODIC MULTI LAYER BASE

Silicon cap layer	<u>215</u>
SiGeC - no boron	<u>213</u>
SiGe - no carbon, no boron	<u>211</u>
SiGe - boron doped	209
SiGe - no carbon, no boron	<u>207</u>
SiGeC - no boron	205
Silicon seed layer	203
p-type silicon substrate with collector region	201.

S<sup>200</sup>

Fig.\_ 2

(57) Abstract: A method and resulting electronic device utilizing periodic multi-layer (ML) (500) and/or superlattice (SL) structures in the base of a SiGe heteroj unction bipolar transistor (HBT) is disclosed. The SL is a special case of an ML, in which layers that are chemically different from adjacent neighbors are successively repeated. The use of the ML (500) in electronic and photonic devices enables strategic engineering of the energy band gap (551, 553) and carrier mobilities. Principles disclosed herein relate to npn- and pnp-type SiGe HBTs as well as HBTs made with other compound semiconductor materials (e.g., other Group III-V or II-VI materials). Additionally, technology and methods disclosed herein benefit other devices types such as, for example, metal oxide semiconductor field effect transistors (MOSFETs), high electron mobility transistors (HEMTs), high hole mobility transistors (HHMTs), bipolar junction transistors (BJTs), and FINFETs.



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A. CLASSIFICATION OF SUBJECT MATTER						
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Hana	277 (1.27					
USPC: 257/187 According to International Patent Classification (IPC) or to both national classification and IPC						
B. FIELDS SEARCHED						
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U S. : 257/187						
Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched						
Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)						
C. DOC	JMENTS CONSIDERED TO BE RELEVANT	<del>.</del>				
Category *	Citation of document, with indication, where a	ppropriate,	of the relevant passages	Relevant to claim No.		
X	US 6,759,694 B1 (Hsu et al.) 06 July 2004 (06.07.20	004), figs	1-6 and col. 1, lines 44-64;	1-17		
A	col. 3, line 8-col. 5, line 50.			18-22		
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<b>D</b> Further	documents are listed in the continuation of Box C		See patent family annex.	_		
* S	pecial categories of cued documents	'T"	later document published after the interdate and not in conflict with the applica			
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